



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ted Johansson et al.

Serial No.: **10/757,092**

Filing Date: **January 14, 2004**

Title: **Selective Base Etching**

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Group Art Unit: **1762**

Examiner:

Attny. Docket No. **068758.0157**

Client Ref.: **01196US/RF/RF**

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INFORMATION DISCLOSURE STATEMENT

Sir:

Applicants respectfully request, pursuant to 37 C.F.R. §§1.56, 1.97 and 1.98, that the art listed on the attached PTO-1449 form be considered and cited in the examination of the above-identified application. A copy of the cited art is enclosed for the convenience of the Examiner.

Furthermore, pursuant to 37 C.F.R. §§1.97(g) and (h), no representation is made that these references are material to the patentability of the present application.

As the Information Disclosure Statement is being submitted before the mailing of the first office action on the merits, Applicants believe that no fee is required. If a fee is

required, please accept this transmittal as a petition therefor and charge any fee to Baker Botts L.L.P. (formerly, *Baker & Botts, L.L.P.*) Deposit Account No. 02-0383, Order No. (068758.0157) for any other charges necessary for the filing of this Information Disclosure Statement.

BAKER BOTTS L.L.P. (023640)

Date: April 26, 2004

By: 

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PTO-1449	Application No. 10/757,092	Applicant(s): Ted Johansson et al.	
	Docket Number 068758.0157	Group Art Unit 1762	Filing Date January 14, 2004

U.S. PATENT DOCUMENTS

		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	1	4,988,632	01-29-91	Pfiester	437	31	01-02-90
	2	5,213,989	05-25-93	Fitch et al.	437	31	06-24-92
	3	5,266,504	11-30-93	Blouse et al.	437	31	03-26-92
	4	5,502,330	03-26-96	Johnson et al.	257	588	06-07-95
	5	5,592,017	01-07-97	Johnson	257	554	06-07-95
	6	5,616,508	04-01-97	Johnson	438	350	01-09-95
	7	6,077,752	06-20-00	Norström	438	309	05-19-98
	8	6,255,183	07-03-01	Schmitz et al.	438	309	04-22-98

FOREIGN PATENT DOCUMENTS

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	9	SE0103726-6	07-01-03	SWEDEN	H01L	21/331	x	
	10	WO 97/19465	05-29-97	PCT	H01L	21/316	x	

NON-PATENT DOCUMENTS

		DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
	11	B. Tillack et al.; "Monitoring of deposition and dry etching of Si/SiGe multiple stacks"; J. Vac. Sci. Technol. B14(1)9, pp. 1184-1198	Jan/Feb 1996
	12	Tsu-Jae King et al.; "A Polycrystalline-Si _{1-x} Ge _x -GATE CMOS Technology"; Center for Integrated Systems, Stanford University, Stanford, CA	4/1990
	13	E. Josse, et al.; "High performance 0.1 μ m MOSFETs with optimized poly-Si and poly-SiGe gates"	
	14	J.A. Babcock et al.; "Precision electrical Trimming of Very Low TCR Poly-SiGe Resistors" IEEE Electron Device Letters. Vol. 21, No. 6	June, 2000
	15	S. Wolf et al.; "for the VLSI Era"; volume 1 – Process Technology; p. 565-567	
	16	D. L. Harame; et al.; "Si/SiGe Epitaxial-Base Transistors-Part II: Process Integration and Analog Applications" IEEE Transactions on Electron Devices, Vol. 42, No. 3	March 1995
	17	T.H. Ning, et al.; "Self-Aligned NPN Bipolar Transistors"; International Electron Devices Meeting; Washington, D.C.	December 1980

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.